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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		APPLICANT Aaron Scott Lukas, et al.	
(37 CFR 1.98(b))		FILING DATE	GROUP

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

		A. Hozumi, et al., "Low-Temperature Elimination of Organic Components from Mesostructured Organic-Inorganic Composite Films Using Vacuum Ultraviolet Light, <i>Chem. Mater.</i> 2000, 12, 3842-3847.
		M. Ouyang, et al., "Conversion of Some Siloxane Polymers to Silicon Oxide by UV/Ozone Photochemical Processes, <i>Chem Mater.</i> 2000, 12, 1591-1596.
		A. Hozumi, et al., "Micropatterned Silica Films with Ordered Nanopores Fabricated through Photocalcination, National Institute of Advanced Industrial Science & Technology, Volume 1, Number 8, August 2001.
		T. Clark, Jr., et al., "A New Application of UV—Ozone Treatment in the Preparation of Substrate-Supported,Mesoporous Thin Films, <i>Chem Mater.</i> 2000, 12, 3879-3884.
		Q. Han, et al., "Ultra Low-k Porous Silicon Dioxide Films from a Plasma Process," IEEE (2001), pp. 171-173.
		C. Waldfried, et al., "Single Wafer RapidCuring™ of Porous Low-k Materials," IEEE (2002), pp. 226-228.

EXAMINER

DATE CONSIDERED

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